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Pursuit of Perfection: Metrology & Yield for Semiconductor Fabrication

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Overview

- What is yield?
- Who cares?
- Apple's Yield Bounty
- Process Control is king
- Beating the System
- One Man's Trash
- Measure twice, cut once
- Review

What is yield?

- Yield refers to the percentage successfully manufactured devices coming out of a manufacturing process
- Manufacturers try to increase yield, effectively reducing the price of a final product

Percent Yield

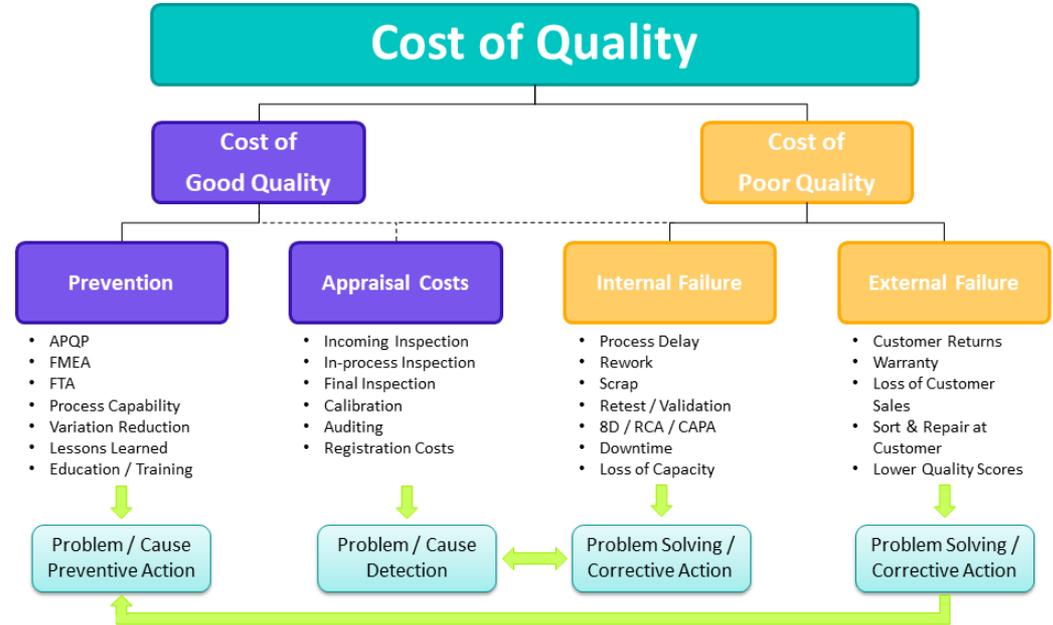
$$\% \text{ Yield} = \frac{\text{Actual Yield}}{\text{Theoretical Yield}} \times 100\%$$

Who cares?

- ~~Time is money~~
- Money is money
- CoGQ << CoPQ
- Managers, quality engineers, and ultimately every employee should care (Bonuses, salary, etc)
- This is a really strong metric to determine whether you're at a "good" company!



Cost of Quality Example



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Apple's Yield Bounty

- TSMC typically charges ~\$20k per wafer produced at 3nm node, regardless of yield (This becomes the customer's problem)
- 200 dies per wafer -> \$100/die (Assumed cost)
- Early-stage yield ~55%
- What is the new, real cost per die?



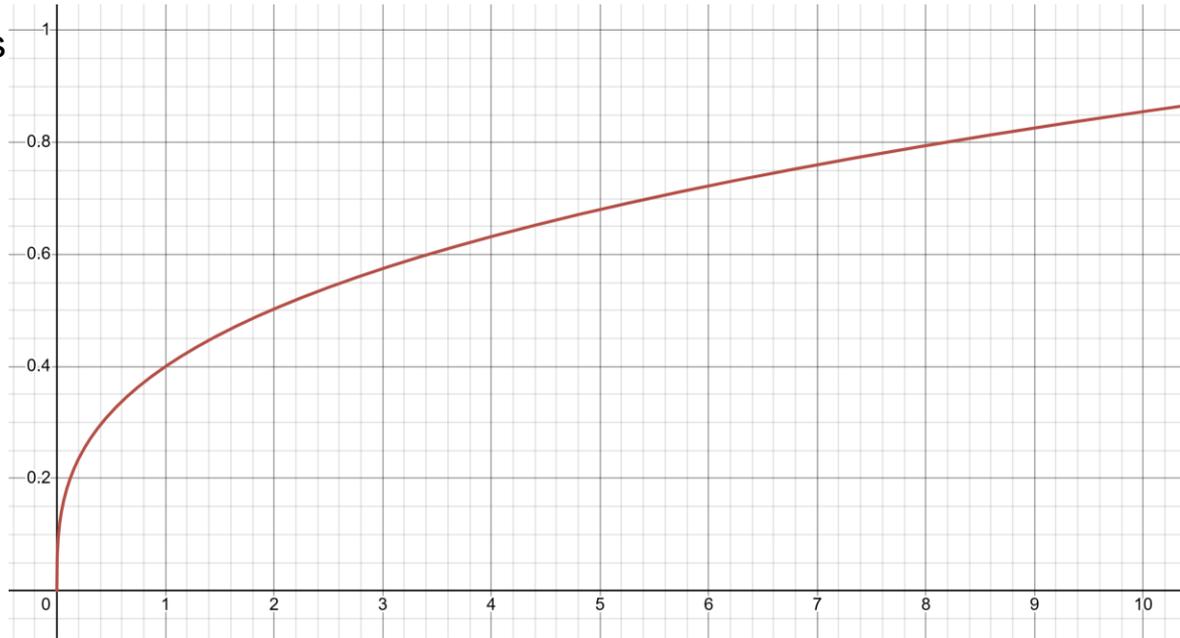
Apple's Yield Bounty

- Apple buys ALL of TSMC's production capability (3nm)... AND have really good lawyers
- TSMC, scared of losing ~75B/yr deal, agreed to sell KGD, until yield could be improved
- Apple removed risk in their product cost, simply because they're big enough to force their supplier into submission
- Deal stood until TSMC reached ~70% yield, before returning to wafer price model

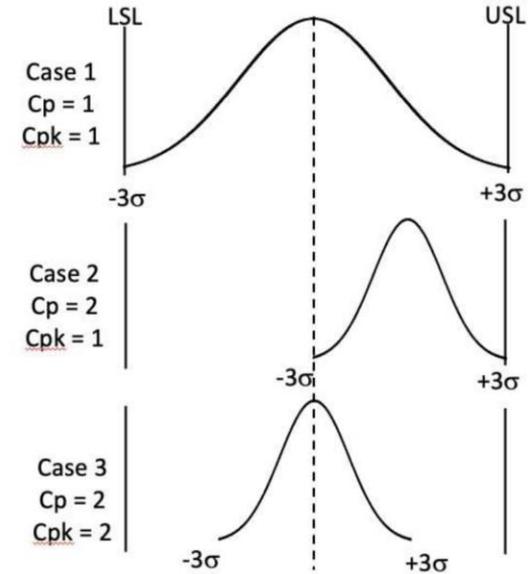
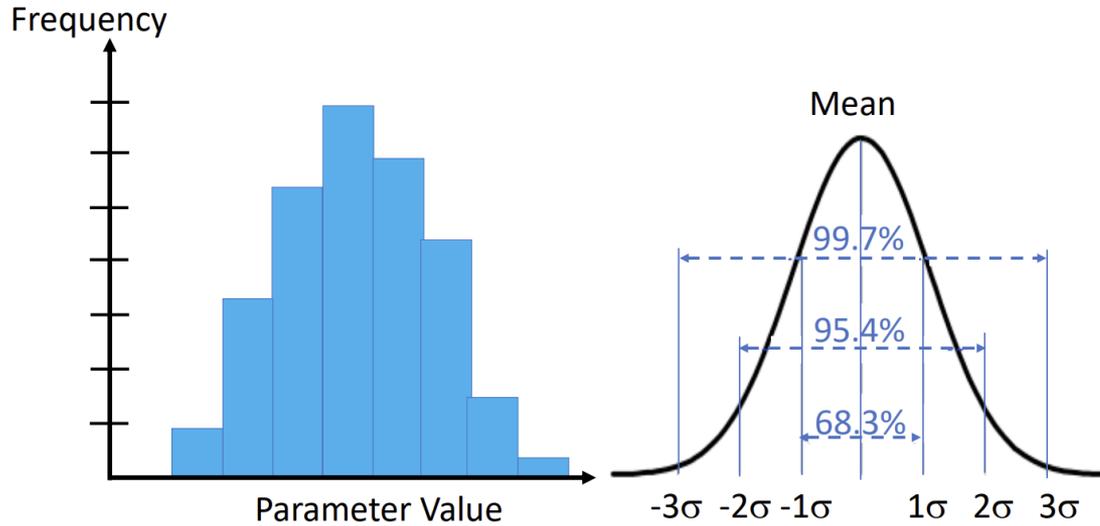


Apple's Yield Bounty

- Yield generally improves over time
- ~90% for mature processes
- ~50% for new processes
- Time, effort required to enable this improvement
- Diminishing returns???



Process Control is King!



$$C_p = \frac{USL - LSL}{6\sigma} \quad (18)$$

$$C_{pk} = \min \left\{ \frac{USL - \bar{X}}{3\sigma}, \frac{\bar{X} - LSL}{3\sigma} \right\}$$

Western Electric (WECO) Rules for Detecting Out Of Control or Non-Random Systems

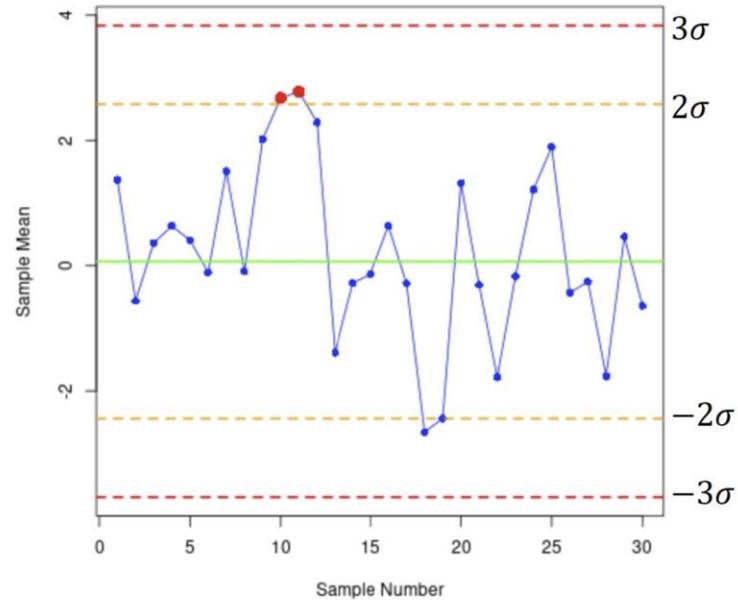
Any one of the following conditions offers evidence that a process is not in control:

- Any point above the upper 3σ or below the lower 3σ control limits
- Two out of the last three points above the upper 2σ or below the lower 2σ control limits
- Four out of the last five points above the upper 1σ or below the lower 1σ control limits
- Eight consecutive points on the same side (above or below) the center line.

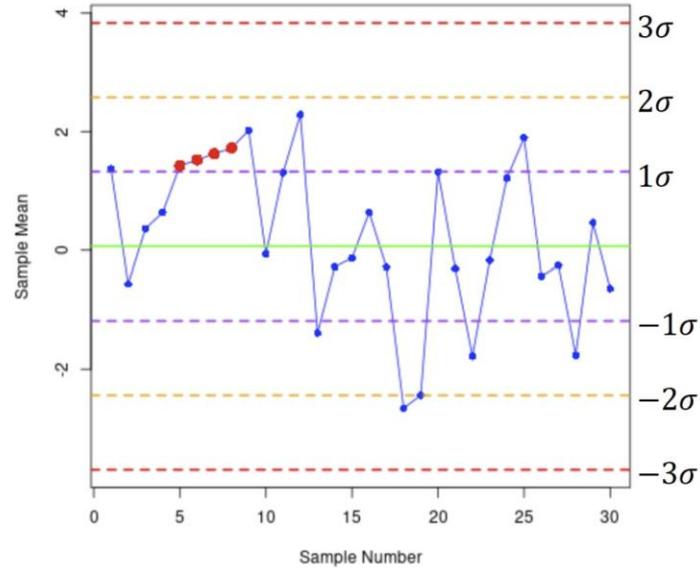
Additional Nelson Rules were developed in the 1950s.

- Six points in a row ascending or descending.
- Fifteen points in a row “hugging” the center line between $+1\sigma$ and -1σ .
- Fourteen points in a row alternating up and down.

Process Control is King!



Process Control is King!



Process Control is King!

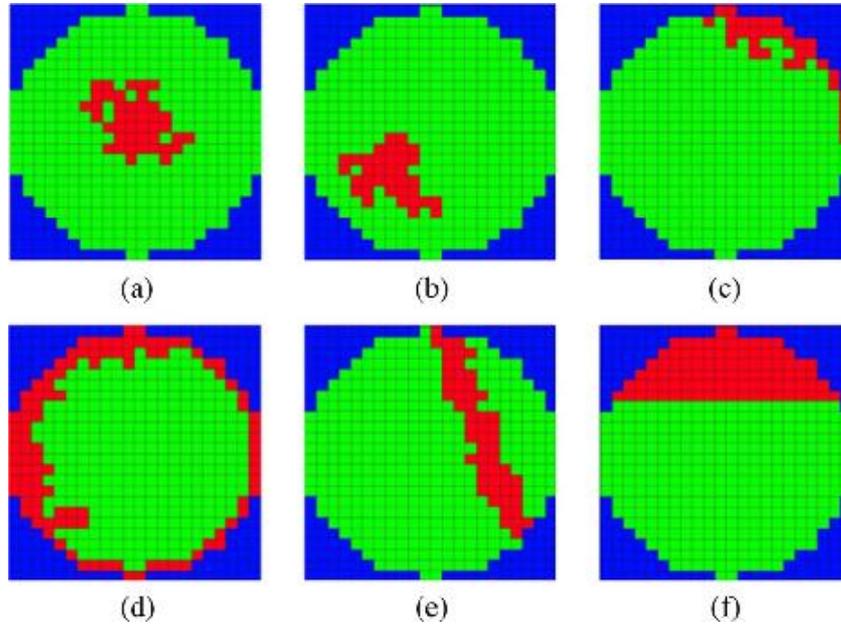
- A powerful formula... Poisson's yield model
- A_c Die area (cm²)
- D_0 Defect density (Defect/cm²)

Lets play with this a bit...

<https://www.desmos.com/calculator/1a1nhlpjzv>

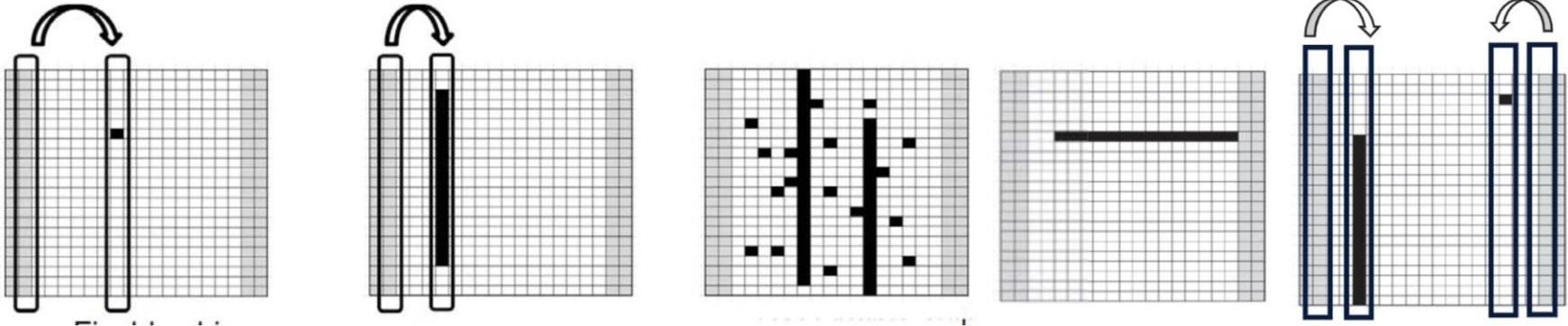
$$Y = \exp(-A_c D_0)$$

Process Control is King!



Beating the system: Redundancy

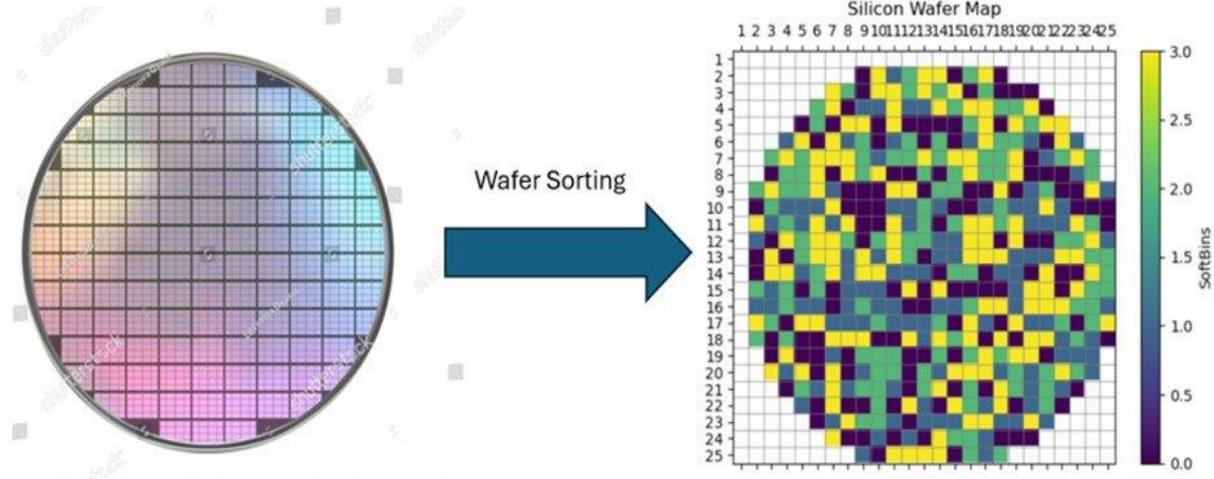
Beating the System as a Designer (Memory)



One Man's trash... (Binning)

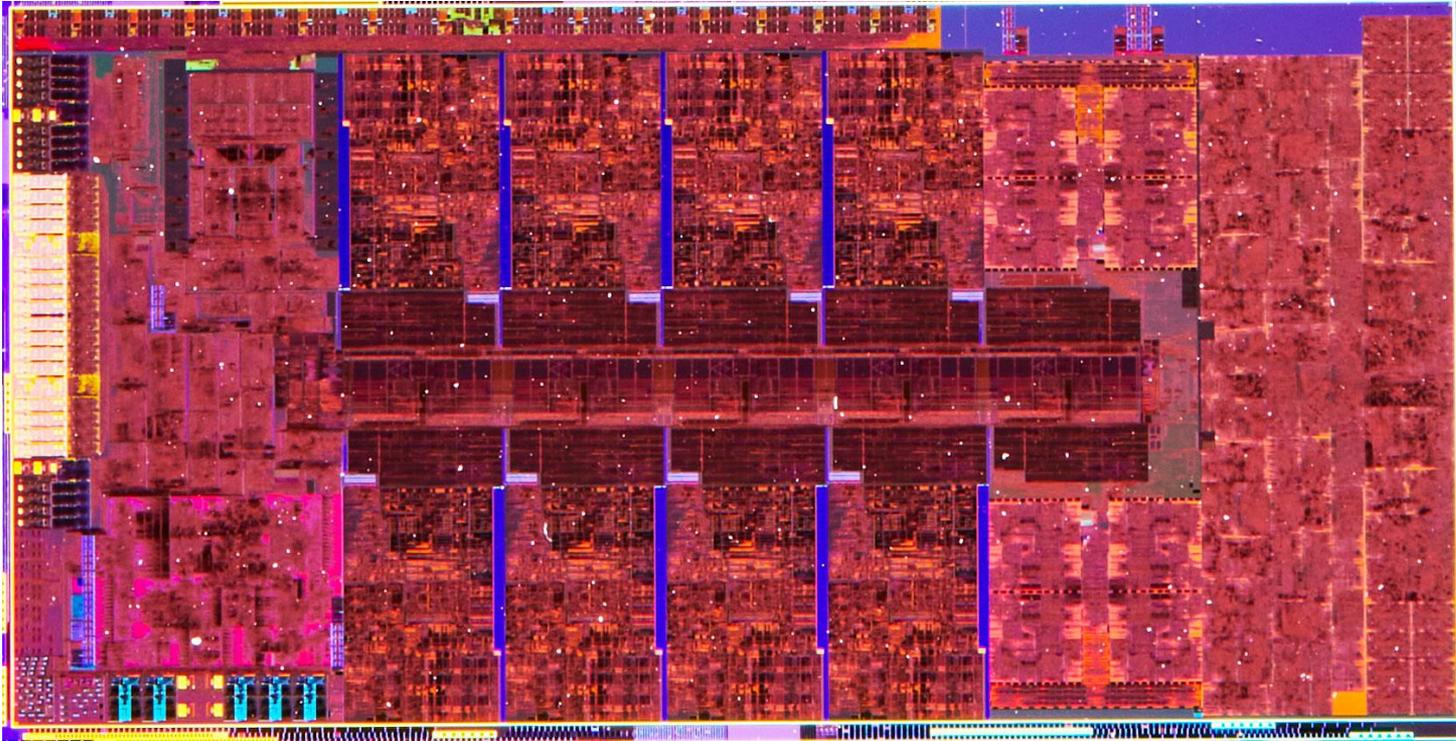


One Man's Trash...



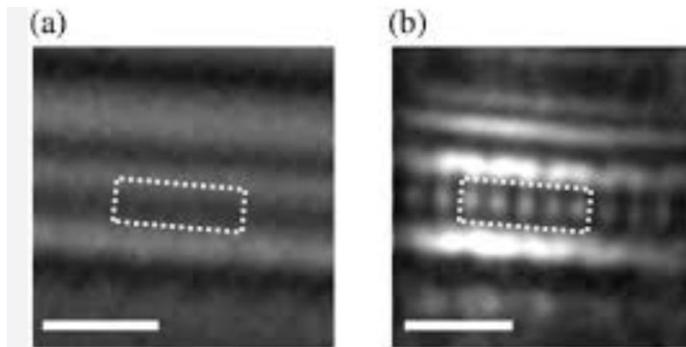
An untested wafer goes through sorting (testing) process. A computer-generated map as a result (right).

One Man's Trash... (12900K -> 12500K)



Measure Twice, Cut Once (Optical Microscopy)

- Fast, Cheap and Efficient
- Imperfect identification of defects
- In-line inspection, can use pattern recognition when scanning over multiple dies
- Bright/dull spots will say “something is probably wrong”
- Better in packaging/large metallization layers
- ~200nm resolution

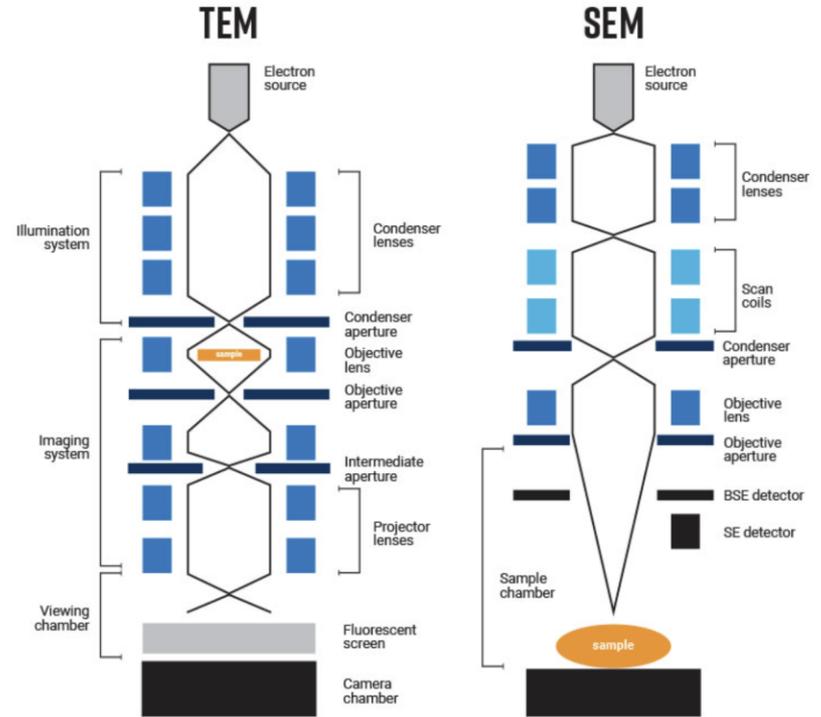


<https://opg.optica.org/ol/fulltext.cfm?uri=ol-45-22-6218&id=442518>



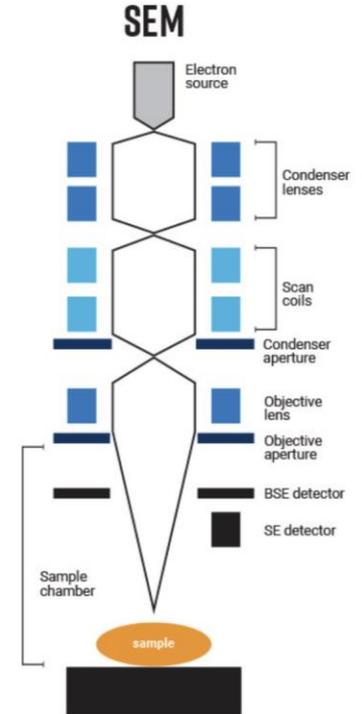
Measure Twice, Cut Once (Electron Beam Microscopy)

- Expensive, hard to put in-line
- Can damage/destroy sample
- Extremely good resolution
- Can potentially see individual atoms
- Too slow for most high volume, in-line applications

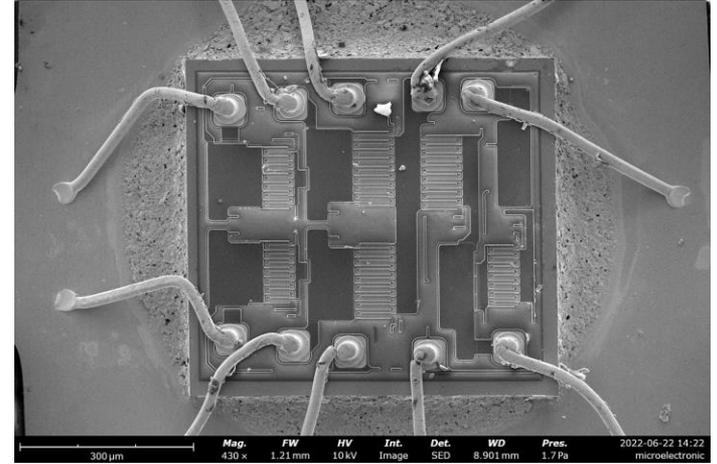
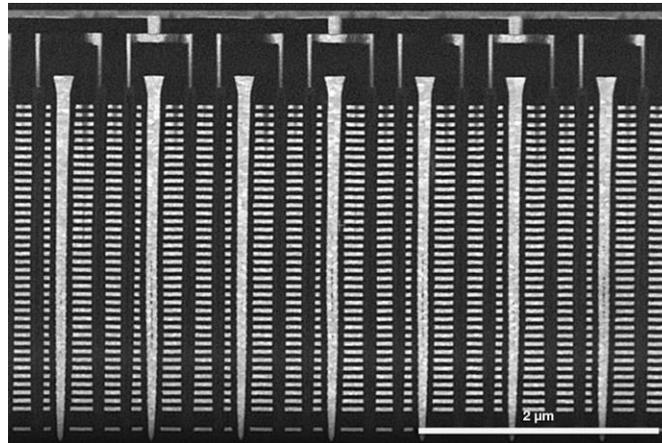
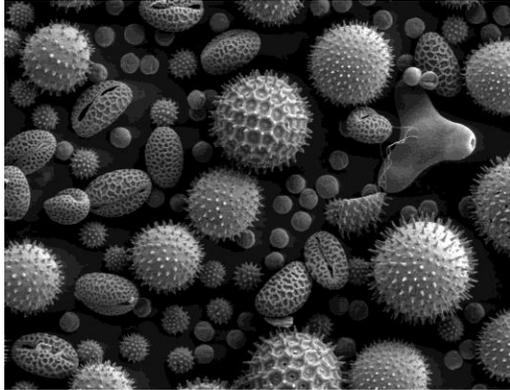


Measure Twice, Cut Once (Scanning Electron-Beam Microscopy)

- Medusa?
- ~1-10 nm resolution
- Higher power = Higher Resolution
- <1kV used by fabs, can use >30kV (Why?)

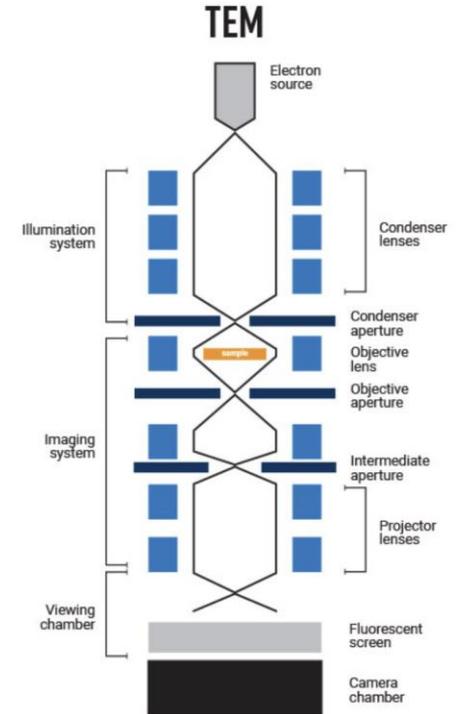


Measure Twice, Cut Once (Electron Beam Microscopy)

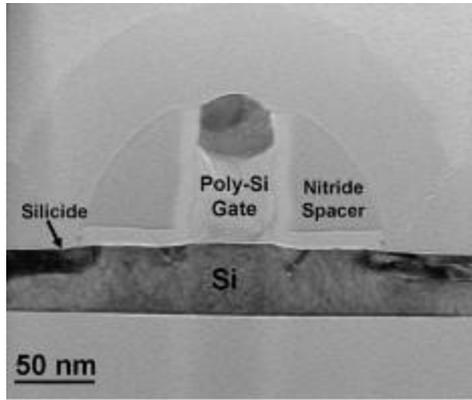


Measure Twice, Cut Once (Transmission Electron-Beam Microscopy)

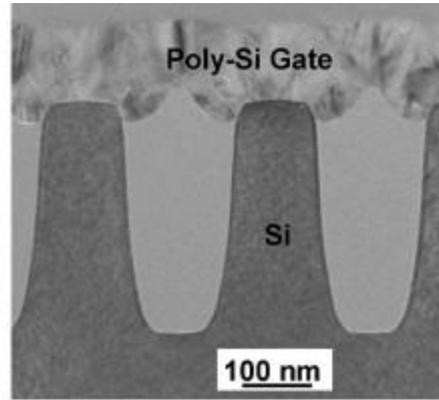
- Semiconductor as glass
- Extremely thin samples
- Sample WILL be destroyed in process (<200nm max thickness)
- Impractical for large sampling requirements
- ~0.1-0.5nm resolution



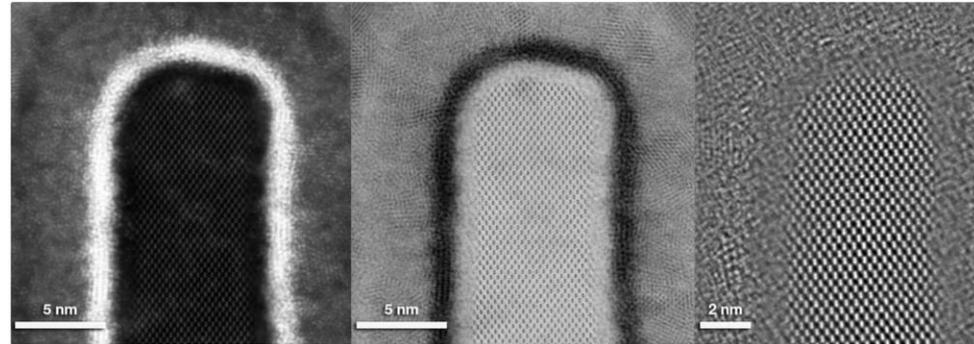
Measure Twice, Cut Once (Electron Beam Microscopy)



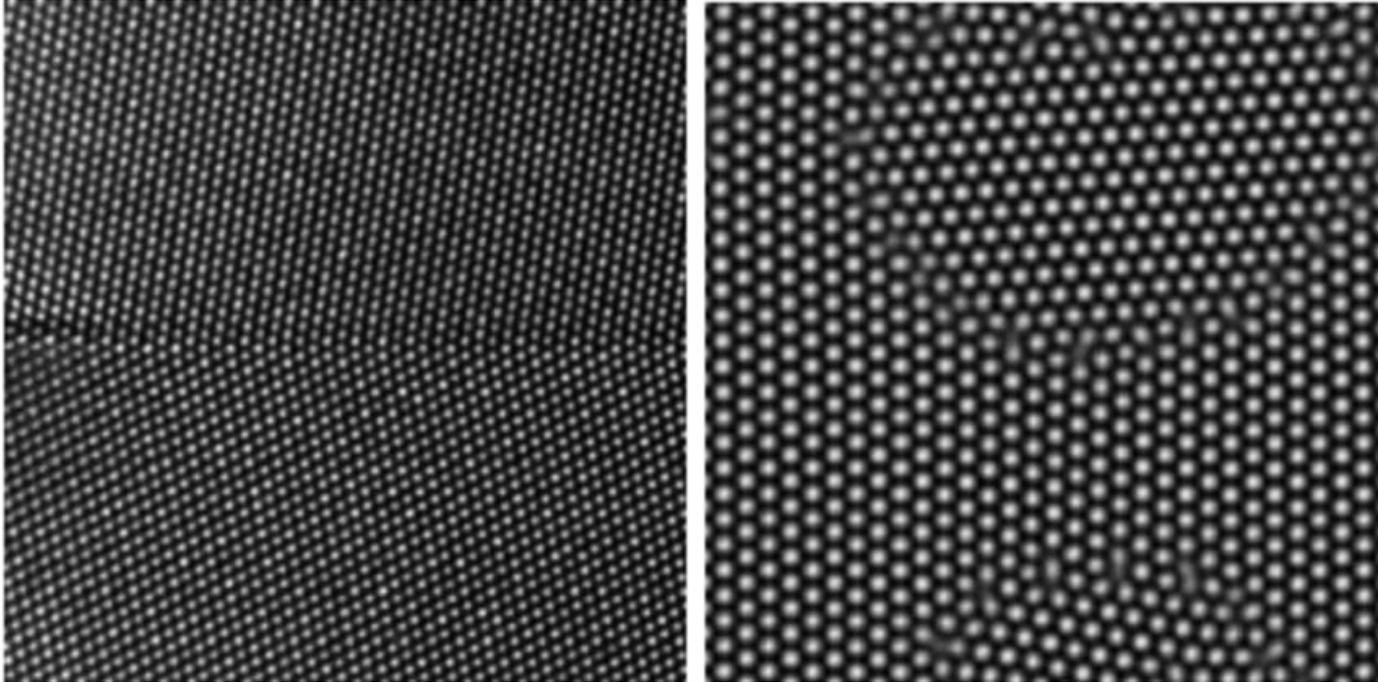
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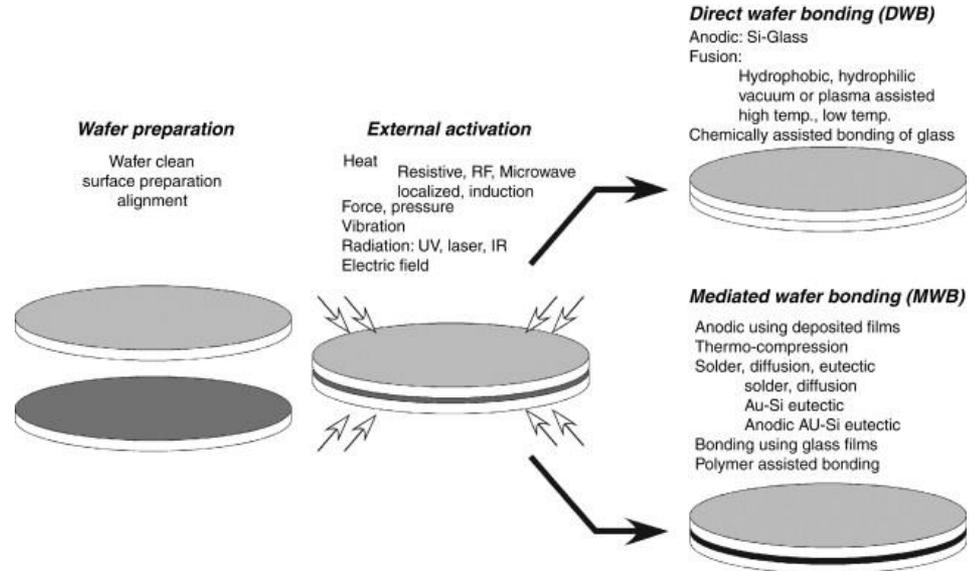
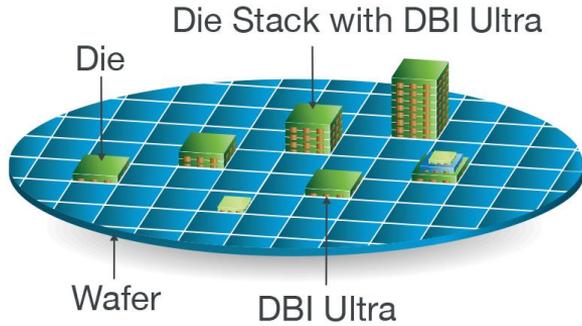
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Measure Twice, Cut Once (Electron Beam Microscopy)



Overview (HI)



Overview

- Fabs cost billions to run.
Increasing yield by a few
%=millions to billions in profit
- Improvement in understanding
of tech
- Upfront cost is typically worth it
- Yield Engineering
- Test Engineering
- Failure Analysis Engineering





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